Electronic Supplementary Information

Precise Regulation of Emissive Layer for Ultra-High Performance White Organic Light-Emitting Diodes in Exciplex Forming Co-host System

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Fig. S1. Proposed energy levels of the organic materials used in our WOLEDs.



Fig. S2. Current density-voltage characteristics of electron-only devices based on orange dopant doped mCBP (a) and PO-T2T (b) host, and hole-only devices based on orange dopant doped mCBP (c) and PO-T2T (d) host. The hole-only device structure: ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP (6 nm) or mCBP: Ir(tptpy)₂acac (4%, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / mCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm), and ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (6 nm) or PO-T2T: Ir(tptpy)₂acac (4%, 6 nm) / mCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm), and ITO / MCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (6 nm) or PO-T2T: Ir(tptpy)₂acac (4%, 6 nm) / mCBP (6 nm) or mCBP: Ir(tptpy)₂acac (4%, 6 nm) / MCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / ITCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm). The electron-only device structure: ITO / Liq (1.5 nm) / PO-T2T (45 nm) / mCBP (6 nm) or mCBP: Ir(tptpy)₂acac (4%, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm) / Al (150 nm), and ITO / Liq (1.5 nm)

nm) / PO-T2T (45 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (6 nm) or PO-T2T: Ir(tptpy)₂acac (4%, 6 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm).



Fig. S3. Current density-voltage characteristics of hole-only (a) and electron-only (b) devices based on mCBP: PO-T2T excipelx and Ir(tptpy)2acac doped mCBP: PO-T2T excipelx. The hole-only device structure: ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T (1:1, 15 nm) or mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:2%, 15 nm) / mCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm). The electron-only device structure: ITO / Liq (1.5 nm) / PO-T2T (45 nm) / mCBP: PO-T2T (1:1, 15 nm) or mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:2%, 15 nm) / mCBP: PO-T2T (1:1, 15 nm) or mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:2%, 15 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm).



Fig. S4. EL performance of WOLEDs with the structure of ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: FIrpic: $Ir(tptpy)_2acac (1:1:10\%:xxx, 15 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm)$ in different $Ir(tptpy)_2acac$ concentrations of 0.3% and 0.5%. (a) Current density and luminance versus driving voltage characteristics. (b) Current efficiency and power efficiency versus luminance characteristics. (c) EQE versus luminance characteristics. Inset: EL spectra of WOLEDs at the luminance of 500 and 10000 cd m⁻².



Fig. S5. PL decay curves of the different films measured at 478 nm (a), 478 nm (b) and 552 nm (c), (d), respectively, with an excitation wavelength of 340 nm. The film structure of KONG+Y is mCBP: PO-T2T (1:1, 12 nm) / mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:1%, 6 nm). The film structure of mCBP: PO-T2T is mCBP: PO-T2T (1:1, 30 nm). The film structure of B+KONG is mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / mCBP: PO-T2T (1:1, 6 nm). The film structure of B+Y is mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / mCBP: PO-T2T (1:1, 6 nm). The film structure of mCBP: 1:1:1%, 6 nm). The film structure of mCBP: Ir(tptpy)₂acac (3%, 20 nm).



Fig. S6. Current density-voltage characteristics of hole-only devices (a) and electrononly devices (b). The hole-only device structure: ITO / HAT-CN (15 nm) / TAPC (60 nm) /TCTA (5 nm) / mCBP (5 nm) / XXX / mCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm). The electron-only device structure: ITO / Liq (1.5 nm) / PO-T2T (45 nm) / XXX / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm). HD1-1 and ED1-1: mCBP: PO-T2T (1:1, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm). HD1-2 and ED1-2: mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:1%, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm). HD2-1 and ED2-1: mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm)/ mCBP: PO-T2T (1:1, 6 nm). HD2-2 and ED2-2: mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm)/ mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:1%, 6 nm).



Fig. S7. EL performance of WOLEDs with the structure of ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: FIrpic (1:1:XXX, 12 nm) / mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:1%, 6 nm)/ PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm) in different concentrations of FIrpic from 0 to 4%. (a) Current density and luminance versus driving voltage characteristics. (b) Current efficiency and power efficiency versus luminance characteristics. (c) EQE versus luminance characteristics. Inset: EL spectra of WOLEDs at the luminance of 1000 cd m⁻².

FIrpic	V _{on} ^a	PE _{max/1000} b	CE _{max/1000} ^b	EQE _{max/1000} ^b		CCT c		
concentration	[V]	[lm W-1]	[cd A ⁻¹]	[%]	Roll-off ₁₀₀₀ ^c	[K]	CIE(x, y) °	CRI °
0	2.4	89.4/42.2	68.7/51.2	20.8/16.2	22.1%	3994	(0.414, 0.498)	44
1%	2.4	95.4/51.5	72.9/60.2	22.1/19.4	12.2%	4428	(0.387, 0.490)	46
2%	2.4	102.0/54.4	78.0/62.8	23.2/20.8	10.3%	4766	(0.368, 0.480)	48
4%	2.4	103.9/58.0	79.4/66.7	23.9/21.9	8.4%	4785	(0.367, 0.481)	48

Table S1. Summary of key EL parameters for white devices with different concentrations of FIrpic.

 $^{\rm a}$ At a luminance of 1 cd m-2; $^{\rm b}$ The maximum efficiencies and values taken at 1000 cd m-2; $^{\rm c}$ Measured at 1000 cd m-2.



Fig. S8. EL performance of WOLEDs with the structure of ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP:Ir(tptpy)₂acac (XXX, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm) in different concentrations of Ir(tptpy)₂acac from 1% to 6%. (a) Current density and luminance versus driving voltage characteristics. (b) Current efficiency and power efficiency versus luminance characteristics. (c) EQE versus luminance characteristics. Inset: EL spectra of WOLEDs at the luminance of 1000 cd m⁻².

Ir(tptpy)2acac	V _{on} ^a	PE _{max/1000} ^b	CE _{max/1000} ^b	EQE _{max/1000} ^b		CCT °		
concentration	[V]	[lm W ⁻¹]	[cd A ⁻¹]	[%]	Roll-off ₁₀₀₀ °	[K]	CIE(x, y) °	CRI °
1%	2.4	81.9/38.9	70.2/56.8	23.3/22.2	4.7%	6725	(0.293, 0.424)	53
2%	2.4	83.8/39.7	72.2/58.2	23.1/21.2	8.2%	5544	(0.332, 0.448)	53
6%	2.4	77.6/38.7	65.3/65.7	20.5/17.9	12.7%	3248	(0.466, 0.505)	37

Table S2. Summary of key EL parameters for white devices with different concentrations of Ir(tptpy)₂acac in mCBP host.

^a At a luminance of 1 cd m⁻²; ^b The maximum efficiencies and values taken at 1000 cd

m⁻²; ^c Measured at 1000 cd m⁻².



Fig. S9. EL performance of WOLEDs with the structure of ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T: Ir(tptpy)₂acac (XXX, 6 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm) in different concentrations of Ir(tptpy)₂acac from 1% to 6%. (a) Current density and luminance versus driving voltage characteristics. (b) Current efficiency and power efficiency versus luminance characteristics. (c) EQE versus luminance characteristics. Inset: EL spectra of WOLEDs at the luminance of 1000 cd m⁻².

Ir(tptpy)2acac	V _{on} ^a	PE _{max/1000} ^b	CE _{max/1000} ^b	EQE _{max/1000} ^b		CCT °		
concentration	[V]	[lm W-1]	[cd A ⁻¹]	[%]	K011-011 ₁₀₀₀ °	[K]	CIE(x, y) °	CRI °
0	2.4	91.9/48.5	70.3/58.2	23.3/22.5	3.4%	7183	(0.278, 0.427)	49
1%	2.4	90.2/51.6	68.9/60.7	21.9/21.2	3.2%	5349	(0.340, 0.457)	53
4%	2.4	86.8/51.4	66.4/59.7	21.1/20.4	3.3%	4305	(0.390, 0.474)	51

Table S3. Summary of key EL parameters for white devices with different concentrations of $Ir(tptpy)_2acac$ in PO-T2T host.

 $^{\rm a}$ At a luminance of 1 cd m-2; $^{\rm b}$ The maximum efficiencies and values taken at 1000 cd

m⁻²; ^c Measured at 1000 cd m⁻².



Fig. S10. EL performance of WOLEDs with the structure of ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T: Ir(tptpy)₂acac (1:1:XXX, 6 nm) / mCBP: PO-T2T: FIrpic (1:1:10%, 12 nm) / PO-T2T (45 nm) / Liq (1.5 nm) / Al (150 nm) in different concentrations of Ir(tptpy)₂acac from 0.5% to 6%. (a) Current density and luminance versus driving voltage characteristics. (b) Current efficiency and power efficiency versus luminance characteristics. (c) EQE versus luminance characteristics. Inset: EL spectra of WOLEDs at the luminance of 1000 cd m⁻².

Ir(tptpy)2acac	V _{on} ^a	PE _{max/1000} ^b	CE _{max/1000} ^b	EQE _{max/1000} ^b		CCT °		
concentration	[V]	[lm W-1]	[cd A ⁻¹]	[%]	Roll-off ₁₀₀₀	[K]	CIE(x, y) °	CRI¢
0.5%	2.4	96.0/48.8	73.4/59.1	22.4/21.8	2.7%	6333	(0.303, 0.438)	52
3%	2.4	88.4/49.8	67.8/62.1	20.9/19.0	9.1%	3315	0.467, 0.519)	34
4%	2.4	86.5/47.5	66.1/60.5	20.8/18.8	9.6%	3160	(0.477, 0.515)	32

Table S4. Summary of key EL parameters for white devices with different concentrations of Ir(tptpy)₂acac in mCBP: PO-T2T host.

 $^{\rm a}$ At a luminance of 1 cd m $^{-2};$ $^{\rm b}$ The maximum efficiencies and values taken at 1000 cd m $^{-2};$ $^{\rm c}$ Measured at 1000 cd m $^{-2}.$



Fig. S11. Current density-voltage characteristics of hole-only (a) and electron-only (b) devices based on mCBP: PO-T2T exciplex host at different phosphors doping. The hole-only device structure: ITO / HAT-CN (15 nm) / TAPC (60 nm) / TCTA (5 nm) / mCBP (5 nm) / mCBP: PO-T2T (1:1, 15 nm) or mCBP: PO-T2T: Ir(ppy)₂acac (1:1:2%, 15 nm) or mCBP: PO-T2T:RD071 (1:1:2%, 15 nm) / mCBP (5 nm) / TCTA (5 nm) / TAPC (60 nm) / HAT-CN (15 nm) / Al (150 nm). The electron-only device structure: ITO / Liq (1.5 nm) / PO-T2T (45 nm) / mCBP: PO-T2T:RD071 (1:1:2%, 15 nm) or mCBP: PO-T2T: Ir(ppy)₂acac (1:1:2%, 15 nm) or mCBP: PO-T2T: Ir(ppy)₂acac (1:1:2%, 15 nm) / mCBP: PO-T2T:RD071 (1:1:2%, 15 nm) or mCBP: PO-T2T: Ir(ppy)₂acac (1:1:2%, 15 nm) or mCBP: PO-T2T:RD071 (1:1:2%, 15 nm) or mCBP: PO-T2T: Ir(ppy)₂acac (1:1:2%, 15 nm) or mCBP: PO-T2T:RD071 (1:1:2%, 15 nm) / PO-T2T (45 nm) / Al (150 nm).



Fig. S12. EL spectra of three-color WOLEDs (W5-8) at different luminance from 500 to 10000 cd m⁻².

Three-color	V _{on} ^a	PE _{max/1000} ^b	CE _{max/1000} ^b	EQE _{max/1000} ^b		CCT °		
device	[V]	[lm W-1]	[cd A ⁻¹]	[%]	Roll-off ₁₀₀₀	[K]	CIE(x, y) ^e	CRI°
W5	2.4	44.3/32.4	40.2/39.2	21.8/19.7	9.6%	2336	(0.512,0.445)	81
W6	2.4	39.2/27.2	34.3/33.3	22.0/19.4	11.8%	1777	(0.554,0.410)	77
W7	2.4	63.0/35.1	52.2/42.2	22.0/17.9	18.6%	3654	(0.432,0.489)	80
W8	2.4	69.6/41.2	55.9/50.3	23.4/22.1	5.6%	4859	(0.361,0.460)	78

Table S5. Summary of key EL parameters for three-color white devices.

 $^{\rm a}$ At a luminance of 1 cd m-2; $^{\rm b}$ The maximum efficiencies and values taken at 1000 cd m-2; $^{\rm c}$ Measured at 1000 cd m-2.